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AMENDMENTS TO THE CLAIMS

1. (Original) An antifuse device for an integrated circuit formed on a substrate, the antifuse device comprising:

a first layer of magnetic material formed on an exposed surface of the substrate;

a second layer of magnetic material positioned above the first layer;

a dielectric layer interposed between the first layer and the second layer wherein the first layer, the second layer and the dielectric layer form an MTJ junction; and

'a logic circuit that is selectable so as to interconnect the first layer to a first electrical potential such that the first and second layers of magnetic material are shorted together when the logic circuit is selected.

- 2. (Original) The device of Claim 1, wherein the first layer comprises a pinned layer of magnetic material that is magnetized in a first fixed direction, the second layer comprises a soft layer of material that can be magnetized in either the first fixed direction or a second direction, and the dielectric layer comprises a tunnel dielectric layer interposed between the first layer and the second layer.
- 3. (Original) The device of Claim 2, wherein the first layer comprises a layer of NiFe that is approximately 100 500Å thick, the second layer comprises a layer of NiFe that is approximately 40 50 Å thick, and the dielectric layer comprises a layer of Al_2O_3 that is approximately 10 15 Å thick.
- 4. (Original) The device of Claim 2, wherein the antifuse device has a resistance of greater than approximately 1 MegaOhm prior to the interconnection to the first electrical potential and wherein the antifuse device, upon interconnection to the first electrical potential is shorted across the tunnel dielectric layer.
- 5. (Original) The device of Claim 4, wherein the selected voltage is approximately 1.8 volts.
- 6. (Original) The device of Claim 1, wherein the antifuse MTJ device further comprises a first barrier layer, a pinning layer, and a second barrier layer.
- 7. (Original) The device of Claim 6, wherein the first barrier layer comprises a layer of Ta that is approximately 50 Å thick, the pinning layer comprises IrMn that is approximately 100 Å thick, and the second barrier layer comprises Ta that is approximately 200 Å thick.
 - 8. 16. (Cancelled).